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PATENT APPLICATION

#8
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10/9/02IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Li et al.

Serial No.: 09/662,682

Filed: September 15, 2000

For: METAL-ASSISTED CHEMICAL
ETCH POROUS SILICON
FORMATION METHOD

Art Unit: 1765

Examiner: Vinh, Lan

)
) I hereby certify that this paper is being deposited with
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Oct. 2, 2002

Date
F-CLASS.WCM

Appr. February 20, 1998

Chy B R
Registration No. 43,874

Attorney for Applicant

RESPONSE BAssistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed August 2, 2002, which has been made
final, please consider the following Remarks.

REMARKS

Claims 1-7, 9, 10-17, 19, and 20 stand rejected under 35 U.S.C. § 103(a) as
being unpatentable over Russell in view of Yoshikawa. Claims 8 and 18 stand rejected under
35 U.S.C. §103(a) as being unpatentable over Russell in view of Yoshikawa, and further in
view of Yamagata. Claim 21 stands rejected under 35 U.S.C. §103(a) as being unpatentable
over Russell in view of Yoshikawa. Applicants respectfully traverse the rejection.

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